

# 2–18 GHz Low Noise Gallium Arsenide FET

## Technical Data

### ATF-13100

#### Features

- **Low Noise Figure:**  
1.1 dB Typical at 12 GHz
- **High Associated Gain:**  
9.5 dB Typical at 12 GHz
- **High Output Power:**  
17.5 dBm Typical  $P_{1\text{ dB}}$  at 12 GHz

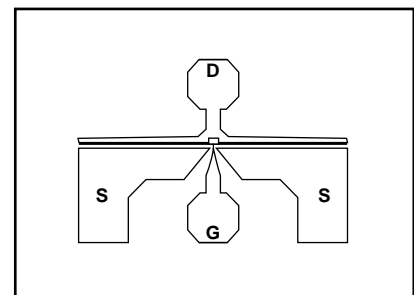
#### Description

The ATF-13100 is a high performance gallium arsenide Schottky-barrier-gate field effect transistor chip. This device is designed for use in low noise, wideband amplifier and oscillator applications in the 2-18 GHz frequency range.

This GaAs FET device has a nominal 0.3 micron gate length with a total gate periphery of 250 microns. Proven gold based metallization systems and nitride passivation assure a rugged, reliable device.

The recommended mounting procedure is to die attach at a stage temperature of 300°C using a gold-tin preform under forming gas. Assembly can be preformed with either wedge or ball bonding using 0.7 mil gold wire. See also “Chip Use” in the APPLICATIONS section.

#### Chip Outline



#### Electrical Specifications, $T_A = 25^\circ\text{C}$

| Symbol            | Parameters and Test Conditions <sup>[1]</sup>   | Units                 | Min. | Typ. | Max. |      |
|-------------------|---|-----------------------|------|------|------|------|
| NF <sub>O</sub>   | Optimum Noise Figure: $V_{DS} = 2.5\text{ V}$ , $I_{DS} = 20\text{ mA}$                 | $f = 8.0\text{ GHz}$  | dB   |      | 0.8  | 1.2  |
|                   |   | $f = 12.0\text{ GHz}$ | dB   |      | 1.1  |      |
|                   |   | $f = 15.0\text{ GHz}$ | dB   |      | 1.5  |      |
| G <sub>A</sub>    | Gain @ NF <sub>O</sub> ; $V_{DS} = 2.5\text{ V}$ , $I_{DS} = 20\text{ mA}$              | $f = 8.0\text{ GHz}$  | dB   | 9.0  | 12.0 |      |
|                   |   | $f = 12.0\text{ GHz}$ | dB   |      | 9.5  |      |
|                   |   | $f = 15.0\text{ GHz}$ | dB   |      | 8.0  |      |
| P <sub>1 dB</sub> | Power Output @ 1 dB Gain Compression<br>$V_{DS} = 4\text{ V}$ , $I_{DS} = 40\text{ mA}$ | $f = 12.0\text{ GHz}$ | dBm  |      | 17.5 |      |
| G <sub>1 dB</sub> | 1 dB Compressed Gain; $V_{DS} = 4\text{ V}$ , $I_{DS} = 40\text{ mA}$                   | $f = 12.0\text{ GHz}$ | dB   |      | 8.5  |      |
| g <sub>m</sub>    | Transconductance: $V_{DS} = 2.5\text{ V}$ , $V_{GS} = 0\text{ V}$                       |                       | mmho | 30   | 55   |      |
| I <sub>DSS</sub>  | Saturated Drain Current; $V_{DS} = 2.5\text{ V}$ , $V_{GS} = 0\text{ V}$                |                       | mA   | 40   | 50   | 90   |
| V <sub>P</sub>    | Pinchoff Voltage: $V_{DS} = 2.5\text{ V}$ , $I_{DS} = 1\text{ mA}$                      |                       | V    | -3.0 | -1.5 | -0.8 |

#### Note:

1. RF performance is determined by assembling and testing 10 samples per wafer.

## ATF-13100 Absolute Maximum Ratings

| Symbol           | Parameter                          | Units | Absolute Maximum <sup>[1]</sup> |
|------------------|------------------------------------|-------|---------------------------------|
| V <sub>DS</sub>  | Drain-Source Voltage               | V     | +5                              |
| V <sub>GS</sub>  | Gate-Source Voltage                | V     | -4                              |
| V <sub>GD</sub>  | Gate-Drain Voltage                 | V     | -6                              |
| I <sub>DS</sub>  | Drain Current                      | mA    | I <sub>DSS</sub>                |
| P <sub>T</sub>   | Power Dissipation <sup>[2,3]</sup> | mW    | 225                             |
| T <sub>CH</sub>  | Channel Temperature                | °C    | 175                             |
| T <sub>STG</sub> | Storage Temperature                | °C    | -65 to +175                     |

**Thermal Resistance:**  $\theta_{jc} = 250^\circ\text{C/W}$ ;  $T_{CH} = 150^\circ\text{C}$   
**Liquid Crystal Measurement:** 1  $\mu\text{m}$  Spot Size<sup>[4]</sup>

### Notes:

1. Permanent damage may occur if any of these limits are exceeded.
2.  $T_{\text{MOUNTING SURFACE}} = 25^\circ\text{C}$ .
3. Derate at 4 mW/°C for  $T_{\text{MOUNTING SURFACE}} > 119^\circ\text{C}$ .
4. The small spot size of this technique results in a higher, though more accurate determination of  $\theta_{jc}$  than do alternate methods. See MEASUREMENTS section for more information.

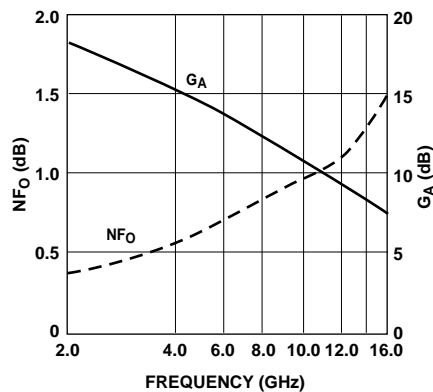
## Part Number Ordering Information

| Part Number   | Devices Per Tray |
|---------------|------------------|
| ATF-13100-GP3 | 50               |

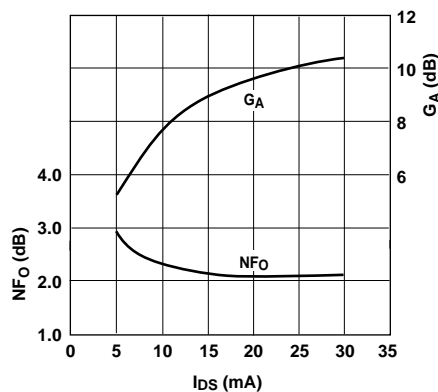
## ATF-13100 Noise Parameters: V<sub>DS</sub> = 2.5 V, I<sub>DS</sub> = 20 mA

| Freq. GHz | NF <sub>O</sub> dB | $\Gamma_{\text{opt}}$ |      | R <sub>N</sub> /50 |
|-----------|--------------------|-----------------------|------|--------------------|
|           |                    | Mag                   | Ang  |                    |
| 4.0       | 0.4                | 0.60                  | 30   | 0.32               |
| 6.0       | 0.7                | 0.32                  | 68   | 0.21               |
| 8.0       | 0.8                | 0.25                  | 102  | 0.15               |
| 12.0      | 1.1                | 0.23                  | -165 | 0.09               |
| 16.0      | 1.5                | 0.32                  | -112 | 0.21               |

## ATF-13100 Typical Performance, T<sub>A</sub> = 25°C



**Figure 1. Optimum Noise Figure and Associated Gain vs. Frequency.**  
V<sub>DS</sub> = 2.5V, I<sub>DS</sub> = 20 mA, T<sub>A</sub> = 25°C.



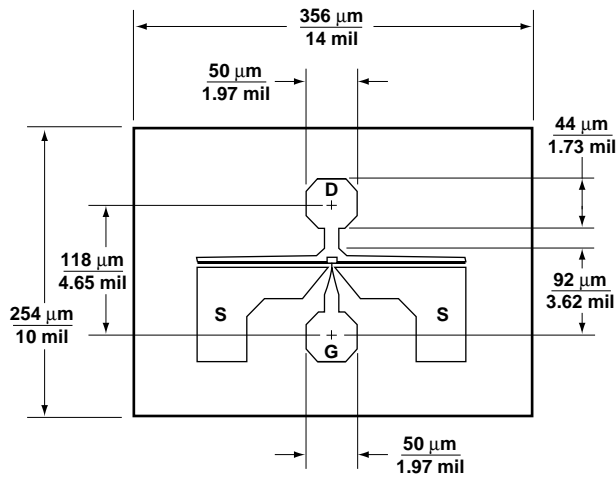
**Figure 2. Optimum Noise Figure and Associated Gain vs. I<sub>DS</sub>.**  
V<sub>DS</sub> = 2.5V, f = 12.0 GHz.

**Typical Scattering Parameters, Common Emitter,  $Z_0 = 50 \Omega$ ,  $T_A = 25^\circ\text{C}$ ,  $V_{DS} = 2.5\text{V}$ ,  $I_{DS} = 20\text{mA}$**

| Freq.<br>GHz | $S_{11}$ |      | dB   | $S_{21}$ |      | dB    | $S_{12}$ |      | $S_{22}$ |      |
|--------------|----------|------|------|----------|------|-------|----------|------|----------|------|
|              | Mag.     | Ang. |      | Mag.     | Ang. |       | Mag.     | Ang. | Mag.     | Ang. |
| 2.0          | .96      | -27  | 13.4 | 4.68     | 153  | -26.9 | .045     | 75   | .55      | -16  |
| 3.0          | .92      | -41  | 13.4 | 4.65     | 140  | -23.6 | .066     | 67   | .52      | -24  |
| 4.0          | .85      | -58  | 13.1 | 4.54     | 126  | -21.4 | .085     | 59   | .49      | -33  |
| 5.0          | .79      | -76  | 12.9 | 4.40     | 113  | -19.8 | .102     | 50   | .44      | -41  |
| 6.0          | .73      | -95  | 12.4 | 4.19     | 100  | -18.7 | .116     | 42   | .38      | -48  |
| 7.0          | .68      | -113 | 12.0 | 3.97     | 87   | -18.0 | .126     | 34   | .30      | -54  |
| 8.0          | .63      | -132 | 11.4 | 3.71     | 75   | -17.5 | .134     | 25   | .24      | -64  |
| 9.0          | .62      | -151 | 10.9 | 3.51     | 63   | -17.1 | .140     | 18   | .18      | -75  |
| 10.0         | .59      | -167 | 10.3 | 3.27     | 53   | -16.8 | .144     | 11   | .13      | -84  |
| 11.0         | .59      | 173  | 9.7  | 3.07     | 40   | -16.5 | .149     | 2    | .08      | -104 |
| 12.0         | .57      | 155  | 9.0  | 2.83     | 30   | -16.5 | .150     | -9   | .02      | 160  |
| 13.0         | .60      | 136  | 8.6  | 2.69     | 19   | -16.4 | .151     | -16  | .08      | 106  |
| 14.0         | .64      | 116  | 7.9  | 2.47     | 7    | -16.4 | .151     | -25  | .15      | 103  |
| 15.0         | .67      | 98   | 7.1  | 2.26     | -6   | -16.4 | .152     | -34  | .23      | 100  |
| 16.0         | .73      | 83   | 5.8  | 1.96     | -16  | -16.9 | .143     | -40  | .31      | 90   |
| 17.0         | .77      | 72   | 4.6  | 1.70     | -26  | -17.0 | .141     | -45  | .36      | 82   |
| 18.0         | .80      | 63   | 3.5  | 1.50     | -35  | -17.4 | .135     | -48  | .40      | 72   |

A model for this device is available in the DEVICE MODELS section.

**ATF-13100 Chip Dimensions**



Note: Die thickness is 4.5 mil, and backside metallization is 200 Å Ti and 2000 Å Au.